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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney Docket No. 20228-0013US1	Application No. 10/580,698	
Information Disclosure Statement by Applicant		Applicant Damian Fiolka et al.		
(Use several she	ets if necessary)	Filing Date	Group Art Unit	
(37 CFR §1.98(b))		November 29, 2006	2872	

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Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	1	7,170,289	1/30/2007	Bievenour et al.			
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	4	JP H06-188169	7/8/1994	ЈРО			X	
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	11	Copy of Chinese Office Action, with English translation, for the corresponding Chinese Application			
	11	No. 2010-10155323.X, dated <b>January 20, 2011.</b>			
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Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if no	t in conformance and not considered. Include copy of this form with
next communication to applicant.	